

A1  
Cont.

feature printed on said structure.

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8. (Amended) A method of trimming a conductor on a substrate, comprising:

providing a conductor having a first critical dimension;

forming a lithographic pattern on said conductor;

etching said conductor with an O<sub>2</sub>-containing material to trim said first critical dimension to a second critical dimension, said second critical dimension being smaller than said first critical dimension; and

correcting an offset between a nested feature printed on said structure and an isolated feature printed on said structure.

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A2